

# Electrodeposition of Metals onto Aligned Carbon Nanotube Microstructures

**Matthew Diasio**  
**Physics, Rice University**

*NNIN REU Site: Lurie Nanofabrication Facility, University of Michigan, Ann Arbor, MI*

*NNIN REU Principal Investigator: Prof. Anastasios John Hart, Mechanical Engr., and Art and Design, University of Michigan*

*NNIN REU Mentor: Davor Copic, Mechanical Engineering, University of Michigan*

*Contact: mad3@rice.edu, ajohnh@umich.edu, copicd@umich.edu*

## Abstract and Introduction:

Nanocomposites offer a way to create materials with specific properties by ordering components on the nanometer scale. Carbon nanotubes (CNTs) are a particularly attractive choice for composites due to their small diameter and outstanding mechanical and electrical properties. Previous studies on CNT-metal composites codeposited the components, resulting in materials with a low concentration of randomly oriented CNTs.

We investigated electrodeposition directly onto vertically aligned CNTs as a means to realize nickel-CNT and copper-CNT composites, and attempted to optimize the procedure to produce uniform composite microstructures. The aligned nature of our structures could greatly enhance the composite's properties compared to randomly oriented CNT composites. Electrodeposition was performed at current densities ranging from approximately 2.5 to 500 mA/cm<sup>2</sup>, with deposition occurring consistently at densities above 25 mA/cm<sup>2</sup> and composites becoming uniform above 100 mA/cm<sup>2</sup>. Morphologies ranged from isolated nanoparticles on CNTs at low current density to thick coatings at high current densities. Infiltration of metal to the interior of the CNT forest was observed under some conditions, and is still under investigation. Future studies will characterize properties of the nickel (Ni) composites for mechanical applications and the copper (Cu) composites for electrical and thermal applications.

## Methods:

The CNT structures were produced by thermal chemical vapor deposition on iron catalyst over an aluminum oxide layer (Al<sub>2</sub>O<sub>3</sub>). Figure 1 shows the process of growing CNTs. Unpatterned substrates resulted in thin, aligned CNT films called "forests." Patterned CNT structures would be produced by photolithographic patterning of the aluminum oxide and iron layers. Patterned structures would be densified by condensation and evaporation of acetone before metal deposition [2]. Some CNTs were plasma etched in argon before deposition. Electrochemical deposition of Ni and Cu occurred in proprietary electroplating solutions.

## Results:

Ni-CNT composites were studied more extensively due to greater ability to control the deposition. Ni nanoparticles were found on CNTs at deposition current densities as low as 12.5 mA/cm<sup>2</sup>, but consistent coating was only noticed at 25 mA/cm<sup>2</sup> or greater. Below 100 mA/cm<sup>2</sup>, Ni nanoparticles could be found regularly on the surface of non-etched CNT structures, but the deposition was not a uniform thin film coating, as seen in Figure 2a.

The density of Ni nanoparticles was greater near the top of a bundle of CNTs than the bottom on non-etched structures. This is believed to be due to plating on the unorganized "crust" of horizontal CNTs at the top that remains from the crowding phase of growth. At equivalent low current densities and deposition run times, plasma etched CNTs showed less deposition or as Figure 2b shows, none at all, compared to non-etched structures. At current densities of 100 mA/cm<sup>2</sup> and greater, the external surfaces of etched and non-etched structures varied less. However, nickel was only found to penetrate

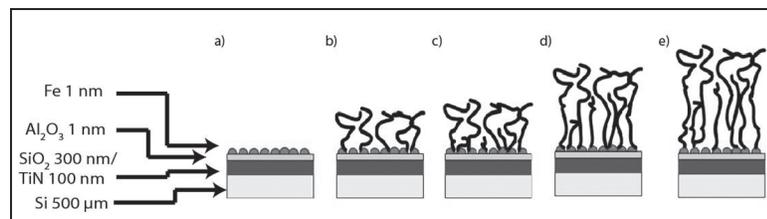


Figure 1: a) Wafer preparation. b) Crowding of CNTs results in c) organization and d) vertical growth until e) termination.

